



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/652,550
Filing Date August 31, 2000
Inventor Keiji Jonoi et al.
Assignee KMT Semiconductor, LTD
Group Art Unit 2811
Examiner Quang D. Vu
Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMS

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT


References -See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on
the attached Form PTO-1449, copies of which are attached. No admission is
made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 3-10-03

By: 
D. Brent Kenady
Reg. No. 40,045



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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. Filed Concurrently Herewith
Filing Date Filed Concurrently Herewith
Inventor Keiji Jono et al.
Assignee Micron Technology, Inc. and KMT Semiconductor, LTD
Group Art Unit Unknown
Examiner Unknown
Attorney's Docket No. KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMS

INFORMATION DISCLOSURE STATEMENT

References - - See attached Form PTO-1449

The citations listed, copies attached, may be material to the examination of the
subject application and are therefore submitted in compliance with the duty of
disclosure defined in 37 CFR §1.56. The Examiner is requested to make these citations
of official record in this application. No admission is made regarding whether all the
submitted references are prior art.

The listed references are discussed in the specification under the heading
"Background of the Invention".

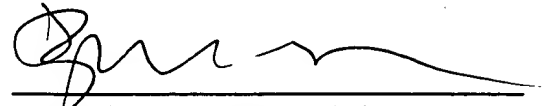
The materials cited are presented to assist in and expedite examination of this
application. The present invention is considered to be patentable over the cited
materials. Expeditious examination and allowance of this application as a patent are
therefore urged in order that the public may benefit from the disclosure and
commercialization of the invention.

1 Citation of these references is respectfully requested.

2 Respectfully submitted,

3
4 Dated: Aug 31, 2000

5 Attorney:


Frederick M. Fliegel, Ph.D.
Reg. No.: 36,138